



제 31회 한국반도체학술대회

The 31st Korean Conference on Semiconductors

2024년 1월 24일(수)-26일(금) | 경주화백컨벤션센터(HICO)

2024년 1월 25일(목), 10:55-12:40

Room I(203), 2층

D. Thin Film Process Technology 분과

[TI2-D] Memory Capacitors

좌장: 전우진 교수(경희대학교), 이홍섭 교수(경희대학교)

초청발표 TI2-D-1 10:55-11:25	High-Performance Nanostructured Flexible Capacitor by Plasma-Assisted Atomic Layer Annealing at Low Temperature Jaehyeong Lee ¹ , Dohyun Go ¹ , Useng Lee ¹ , Jong. G Ok ¹ , and Jihwan An ² ¹ Department of Manufacturing Systems and Design Engineering, SeoulTech, ² Department of Mechanical Engineering, POSTECH
TI2-D-2 11:25-11:40	Low Temperature Crystallization of Atomic Layer Deposited SrTiO ₃ Films with Minimal Interfacial Reactions Hong Keun Chung ^{1,2} , Tae Joo Park ² , and Seong Keun Kim ^{1,3} ¹ Electronic Materials Research Center, KIST, ² Department of Materials Science and Chemical Engineering, Hanyang University, ³ KU-KIST Graduate School of Converging Science and Technology, Korea University
TI2-D-3 11:40-11:55	Improvement of Electrical Properties of ZrO ₂ /Al ₂ O ₃ Capacitors via Interfacial Defect Control Using Ar Plasma Treatment Hyeongjun Kim and Woongkyu Lee Department of Green Chemistry and Materials Engineering and Department of Materials Science and Engineering, Soongsil University
TI2-D-4 11:55-12:10	The Precise Control of the Interfacial Reactions in TiO ₂ /RuO ₂ -structured Capacitors for DRAM Applications Jihoon Jeon ^{1,2} , Taiky Kim ¹ , Myungsu Jang ^{1,2} , Hong Keun Chung ¹ , and Seong Keun Kim ^{1,2} ¹ Electronic Materials Research Center, KIST, ² KU-KIST Graduate School of Converging Science and Technology, Korea University
TI2-D-5 12:10-12:25	Fabrication of MoO ₂ Electrode by Thermal Atomic Layer Deposition for High-performance TiO ₂ -Based DRAM Capacitors Jae Hyeon Lee, Wangu Kang, Jeong Eun Shin, and Jeong Hwan Han Department of Materials Science and Engineering, Seoul National University of Science and Technology



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TI2-D-6 12:25-12:40	Plasma-enhanced Atomic Layer Deposition of TiN/Mo ₂ N Stacks for Advanced Storage Nodes in Next-generation DRAM Capacitors Wangu Kang, Ji Sang Ahn, Ha Young Lee, Byung Joon Choi, and Jeong Hwan Han Department of Materials Science and Engineering, Seoultech
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